

<b>Form PTO-1449</b> <b>LIST OF PRIOR ART CITED BY APPLICANT</b>		ATTORNEY DOCKET NO. <b>AUS9-1999-0269-US1</b>		SERIAL NO. <b>09/ 703,335</b>	
		APPLICANT <b>Berstis et al.</b>			
		FILING DATE <b>10/31/00</b>		GROUP ART UNIT <b>2841</b>	

jcs17 U.S. PTO  
 09/703335  
 10/31/00

U.S. PATENT DOCUMENTS					
EXAMINER INITIAL	DOCUMENT NO.	PUBLICATION DATE	INVENTOR NAME	CLASS/ SUBCLASS	FILING DATE

FOREIGN PATENT DOCUMENTS					
EXAMINER INITIAL	DOCUMENT NO.	PUBLICATION DATE	COUNTRY	CLASS/ SUBCLASS	TRANSLATION YES NO

OTHER PRIOR ART (including author, title, date, pertinent page, etc.)	
MCL	B. Prince, <u>Semiconductor Memories: A Handbook of Design, Manufacture, and Application</u> , 2nd edition, John Wiley & Sons, pp. 182-187, 07/1996.
MCL	Weinberg, "On tunneling in metal-oxide-silicon structures", <u>J. Appl. Phys.</u> , v. 53, n. 7, pp. 5052-5056, 07/1982.
MCL	Amin, "Design, selection, and implementation of flash erase EEPROM memory cells", <u>IEE Proceedings-G</u> , v. 139, n. 3, pp. 370-376, 06/1992.
MCL	Forbes, "Use of a spreadsheet for Fowler-Nordheim equation calculations", <u>J. Vac. Sci. Technol. B</u> , v. 17, n. 2, pp. 534-541, Mar/Apr. 1999.
MCL	Lenzlinger et al., "Fowler-Nordheim Tunneling into Thermally Grown SiO <sub>2</sub> ", <u>J. Appl. Phys.</u> , v. 40, n. 1, pp. 278-283, 01/1969.
MCL	Masuoka et al., "Reviews and Prospects of Non-Volatile Semiconductor Memories", <u>IEICE Transactions</u> , v. E 74, n. 4, 04/1991.
MCL	Masuoka et al., "Flash Memories, Their Status and Trends", <u>Proceedings of 4th Intl. Conf. on Solid-State and Integrated Circuit Technology</u> , pp. 128-132, 10/1995.
MCL	Chi et al., "True Low-Voltage Flash Memory Operations", <u>Proceedings of 1996 Intl. Nonvolatile Memory Technology Conference</u> , pp. 94-98, 04/1996.

DATE CONSIDERED <b>2/20/02</b>	EXAMINER <i>Michael J. Zuckerman</i>
--------------------------------	--------------------------------------

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP § 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.